# Monthly LabAdviser update: 17/1 2013

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| Updated Subject | Contributer | Link to the update pages |
| **New e-mail template for e-beam requests**  **E-mail request for metal wishes now also for physimeca** | Tine Greibe@ danchipJesper Hanberg @ danchip | <http://labadviser.danchip.dtu.dk/index.php/Template:DanchipInfo> |
| E-beam | Tine Greibe@ danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/E-beam_lithography> |
| **DRIE-pegasus**  Sloped sidewalls | Jonas M. Lindhard @ danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/DRIE-Pegasus/slopedsidewalls> |
| **Wafer info** | Yvonne @ danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Wafer_Information> |
| **Info on some standard masks used at Danchip for QC and development** | Jonas M. Lindhard @ danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Photolithography/masks/travka>  <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Photolithography/masks/travka/fields/Aline> |
| **SEM’s**  Improved overview page | Jonas M. Lindhard @ danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/SEM:_Scanning_Electron_Microscopy> |
| **AOE**  SiO2 etch with Si mask | Berit G. Herstrøm @ danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/Etching_of_Silicon_Oxide/SiO2_etch_using_AOE> |
| **Dry etcher’s**  New comparison page | Jonas M. Lindhard @ danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/ICP> |
| **ICP metal etcher** | Jonas M. Lindhard @ danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/ICP_Metal_Etcher> |